

Vacuum Deposition Technologies and Semiconductor Applications

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Message from the Guest Editors

Dear Colleagues,

Nanoscale thin films play a fundamental role in various applications, encompassing coatings, surface treatments, semiconductor devices, and so on. The deposition of thin films allows for the refinement of elemental surface layers, ensuring specific functional properties while potentially utilizing cost-effective core materials. Among the many techniques enhancing the functional properties of engineering materials surfaces, vacuum methods play an important role in industrial practice. The aim of this Special Issue is to provide a platform where academics, industry experts, and researchers worldwide can share their research achievements and exchange experiences within the field of vacuum deposition and semiconductor applications.

Topics of interest include but are not limited to:

1. Theoretical and experimental research in vacuum thin-film deposition methods;
2. Thin-film processes and related devices, including CVD, PVD and ALD...;
3. The application of vacuum thin-film deposition, including metal oxide semiconductor field effect transistors (MOSFETs), thin-film transistors (TFTs), sensors, ...



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Message from the Editorial Board

Now more than ever, research is asked to deliver knowledge and technologies to solve the major challenges faced by our society. The development of new materials and devices for (without the ambition to be exhaustive) energy, health and food technology, together with the need for establishing processes that reduce the impact on critical resources and the environment, is indeed in the spotlight of most contemporary research. Surface science and engineering play a key role in this regard, with an incredible potential in delivering new and deep scientific understanding and technical solutions essential to solve most of the major societal challenges.

Coatings is a well-established, peerreviewed, online journal dedicated to the vibrant field of surface science and engineering. Coatings publishes original research articles that report cutting-edge results and review papers that make the point on the hottest research topics.

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